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1995:804784 CAPLUS
ΑN
    123:315749
    Preparation of high-purity tetrakisphenolethanes
DN
    Inatomi, Shigeki; Kai, Isao; Mori, Shigeru
ΤI
IN
    Asahi Organic Chem Ind, Japan
PΑ
     Jpn. Kokai Tokkyo Koho, 4 pp.
SO
     CODEN: JKXXAF
     Patent
TG
     Japanese
LА
     ICS B01J027-02; B01J027-06; B01J031-02; B01J031-04; C07C037-20
IC
ICA C07B061-00
     37-6 (Plastics Manufacture and Processing)
     Section cross-reference(s): 74
                                           APPLICATION NO. DATE
FAN.CNT 1
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                                                             19910426
                                           JP 1991-122888
                     A2 19950711
     JP 07173089
ΡI
                      B2 19990531
     The title compds., useful as materials for thermosetting resins, curing
      agents for epoxy resins, ballasts of photosensitive agent for
 AΒ
      photoresists, modifiers for phenolic resins, antioxidants, etc., are
      prepd. in high purity by condensation of phenols with glyoxal in the
      presence of acidic catalysts, concn. of the reaction mixt. to remove
      volatile components, and then treatment of the residual matter with org.
      solvents capable of dissolving low-mol.-wt. compds. and higher
      and acting as poor solvents to the title compds. A mixt. of PhOH,
 condensates
      glyoxal, and p-MeC6H4SO3H was heated under reflux over 1 h and further
      stirred at the reflux temp. for 6 h. Subsequently the reaction mixt. was
      vacuum-concd. and the solid residue was ground and treated with acetone
      under stirring to give 11.3% (4-HOC6H4)2CHCH(C6H4OH-4)2 with purity
      hydroxyphenylethane prepn purifn solvent acetone; THF purifn solvent
 94.48.
      hydroxyphenylethane prepn; ethane tetrakisphenol prepn; phenol
       condensation glyoxal
      (7727-33-5P) 1,1,2,2-Tetrakis(4-hydroxyphenyl)ethane
                                                             108261-54-7P
       RL: IMF (Industrial manufacture); PUR (Purification or recovery); SPN
       (Synthetic preparation); TEM (Technical or engineered material use); PREP
       (Preparation); USES (Uses)
          (prepn. of tetrakisphenolethanes in high purity by acid-catalyzed
          condensation of phenols with glyoxal, concn., and treatment with org.
                                78-93-3, Ethyl methyl ketone, uses
          solvents)
       67-64-1, Acetone, uses 78-93-3, Ethyl methyl ketone, uses Isobutyl methyl ketone 109-99-9, Tetrahydrofuran, uses
  IT
       RL: NUU (Nonbiological use, unclassified); USES (Uses)
          (prepn. of tetrakisphenolethanes in high purity by acid-catalyzed
          condensation of phenols with glyoxal, concn., and treatment with org.
       95-48-7, o-Cresol, reactions 108-95-2, Phenol, reactions
                                                                     108-95-2D,
  IT
       Phenol, derivs.
           (prepn. of tetrakisphenolethanes in high purity by acid-catalyzed
       RL: RCT (Reactant)
          condensation of phenols with glyoxal, concn., and treatment with org.
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solvents)

7727-33-5 REGISTRY Phenol, 4,4',4'',4'''-(1,2-ethanediylidene)tetrakis- (9CI) (CA INDEX RN CN NAME) OTHER CA INDEX NAMES: Phenol, 4,4',4'',4'''-ethanediylidenetetra- (6CI) OTHER NAMES: 1,1,2,2-Tetrakis(4-hydroxyphenyl)ethane CN 1,1,2,2-Tetrakis(p-hydroxyphenyl)ethane CN CN TEP-DF C26 H22 O4 MF IN Files: BEILSTEIN*, BIOSIS, CA, CAOLD, CAPLUS, CASREACT, CHEMCATS, CHEMLIST, IFICDB, IFIUDB, TOXLIT, USPATFULL CI COM STN Files: LC(*File contains numerically searchable property data) EINECS**, NDSL**, TSCA** Other Sources: (**Enter CHEMLIST File for up-to-date regulatory information)

- 59 REFERENCES IN FILE CA (1967 TO DATE)
- 8 REFERENCES TO NON-SPECIFIC DERIVATIVES IN FILE CA
- 59 REFERENCES IN FILE CAPLUS (1967 TO DATE)
- 1 REFERENCES IN FILE CAOLD (PRIOR TO 1967)